

EV633265449



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/669,667
Filing Date September 23, 2003
Confirmation No. 5558
Inventor Li Li et al.
Assignee Micron Technology, Inc.
Group Art Unit 1722
Examiner Felisa Carla Hiteshew
Attorney's Docket No. MI22-2144
Customer No. 021567
Title: Atomic Layer Deposition Methods of Forming Silicon Dioxide
Comprising Layers

RESPONSE TO JUNE 2, 2005 OFFICE ACTION

To: Mail Stop Amendment
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

VIA U.S. EXPRESS MAIL

From: Mark Matkin (Tel. 509-624-4276; Fax 509-838-3424)
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Responsive to the Office Action dated June 2, 2005, Applicant amends
and remarks as follows:

AMENDMENTS